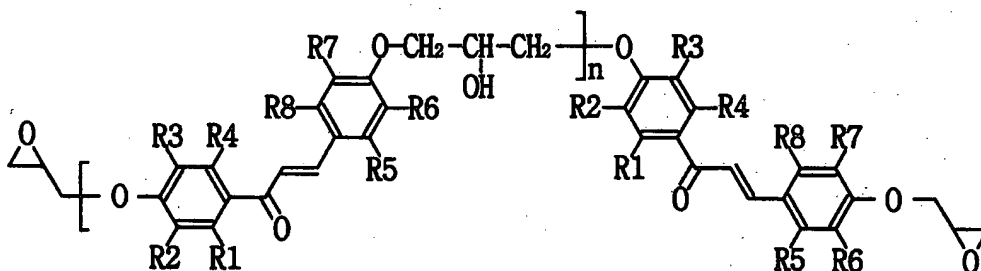


IN THE CLAIMS:

Please amend the claims as follows. No new matter is introduced.

1. (Currently Amended) A compound comprising an epoxy group and a chalcone group represented by the following formula:

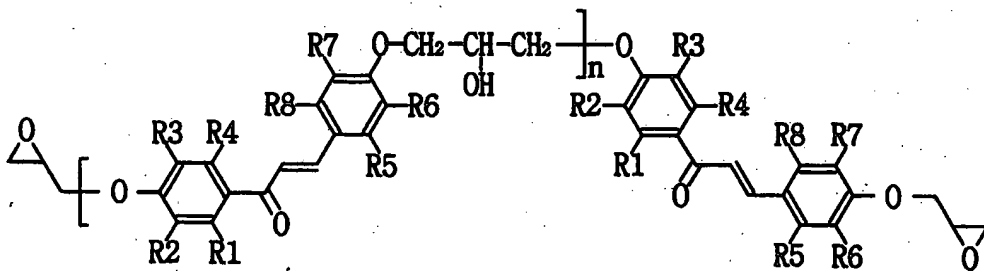


wherein n is an integer from 1 to 10,000, and each of $R_1, R_2, R_3, R_4, R_5, R_6, R_7$ and R_8 is selected from a group consisting of a hydrogen atom, an alkyl group, an alkoxy group, a halogen atom and a nitro group, wherein at least one of $R_1, R_2, R_3, R_4, R_5, R_6, R_7$, and R_8 is the halogen and at least one of $R_1, R_2, R_3, R_4, R_5, R_6, R_7$, and R_8 is the alkoxy group.

2. (Original) The compound according to claim 1, wherein the compound has a weight average molecular weight of about 800 to about 20,000.

3. (Currently Amended) A process for preparing a compound including an epoxy group and a chalcone group comprising:

reacting bis(4-4'-hydroxy) chalcone with ~~epichlorohydrin~~ epichlorohydrin in the presence of an alkali metal salt to synthesize a compound represented by the following formula:



wherein n is an integer from 1 to 10,000, ~~and~~ each of R₁, R₂, R₃, R₄, R₅, R₆, R₇ and R₈ is selected from a group consisting of a hydrogen atom, an alkyl group, an alkoxy group, a halogen atom and a nitro group, wherein at least one of R₁, R₂, R₃, R₄, R₅, R₆, R₇, and R₈ is the halogen and at least one of R₁, R₂, R₃, R₄, R₅, R₆, R₇, and R₈ is the alkoxy group.

4. (Original) The process of claim 3 further comprising reacting bis[4,4'-(2-2'-tetrahydro-2H-pyranoxy)]chalcone with a paratoluene sulfonic acid in the presence of an alcohol to synthesize the bis(4-4'-hydroxy) chalcone.

5. (Currently Amended) The process of claim 4 further comprising reacting 4-(2-tetrahydro-2H-pyranoxy) ~~acetohenone~~ acetophenone with 4-(2-tetrahydro-2H-pyranoxy) benzaldehyde in the presence of an alkali metal salt to synthesize the bis[4,4'-(2-2'-tetrahydro-2H-pyranoxy)]chalcone.

6. (Original) The process of claim 5 further comprising reacting 4-hydroxy benzaldehyde with 3,4 dihydro-2H-pyran to synthesize the 4-(2-tetrahydro-2H-pyranoxy) benzaldehyde.

7. (Original) The process of claim 5 further comprising reacting 4-hydroxy acetophenone with 3,4 dihydro-2H-pyran to synthesize the 4-(2-tetrahydro-2H-pyranoxy) acetohenone.

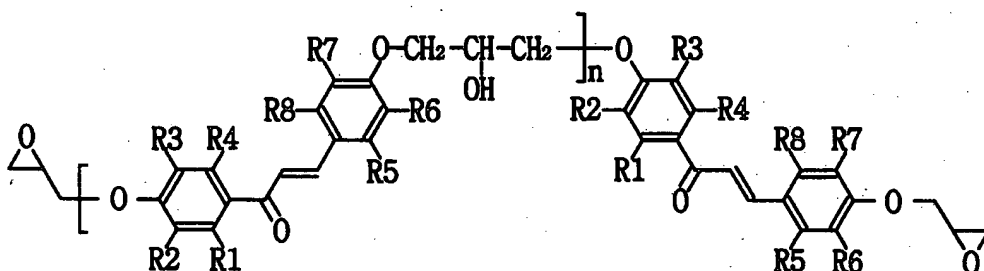
8. (Original) The process of claim 3, wherein the compound has a weight average molecular weight of about 800 to about 20,000.

9. (Currently Amended) The process of claim 4 ~~3~~, wherein the alcohol is ethanol.

10. (Original) The process of claim 3, wherein the alkali metal salt is sodium hydroxide or potassium hydroxide.

11. (Currently Amended) A resist composition comprising:

(a) a compound comprising an epoxy group and a chalcone group represented by the following formula:



wherein n is an integer from 1 to 10,000 and each of R₁, R₂, R₃, R₄, R₅, R₆, R₇ and R₈ is selected from a group consisting of a hydrogen atom, an alkyl group, an alkoxy group, a halogen atom and a nitro group;

(b) an acrylate resin;

(b c) a curing agent; and

(e d) an organic solvent.

12. (Original) The resist composition of claim 11, wherein the resist composition includes about 5 to about 35 parts by weight of the compound, about 0.01 to about 5 parts by weight of the curing agent, and about 60 to about 90 by weight of the organic solvent.

13. (Original) The resist composition of claim 11, wherein the organic solvent is propylene glycol monomethyl ether acetate, ethyl ethoxy acetate, or cyclohexanone.

14. (Canceled)

15. (Currently Amended) The resist composition of claim 11 14, wherein the resist composition includes about 5 to about 35 parts by weight of a combination of the acrylate resin and the compound, about 0.01 to about 5 parts by weight of the curing agent, and about 60 to about 90 by weight of the organic solvent.

16. (Currently Amended) The resist composition of claim 11, further comprising a pigment, wherein the pigment is dissolved in a solvent.

17. (Currently Amended) The resist composition of claim 16, further comprising a dispersant for dispersing the pigment in the photoresist composition.

18. (Currently Amended) The resist composition of claim 11, further comprising a photo-initiator.

19. (Original) The resist composition of claim 18, wherein the photo-initiator is benzil dimethyl ketal, diphenyl(2,4,6-trimethylbenzoyl)phosphine oxide, or bis(trichloromethyl)-s-triazine derivative.

20. (Canceled)

21. (Original) mThe resist composition according to claim 11, wherein the compound has a weight average molecular weight of about 800 to about 20,000.

22. (Original) The resist composition according to claim 16, wherein the pigment is a red, blue, green, yellow, or violet pigment.

23. (Original) The resist composition according to claim 11, wherein the curing agent is a dipentaerithritol hexaacrylate or a trimethylolpropane trimethacrylate.